

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	16165	(electroplat\$ or electro-plat\$ or electrodeposit\$ or electro-deposit\$).clm.	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:53
L2	3134	((electrolyt\$ or electro-lyt\$ or electrochem\$ or electro-chem\$) near2 (deposit\$)).clm.	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:53
L3	3257	((electrolyt\$ or electro-lyt\$ or electrochem\$ or electro-chem\$) near2 (plate or plates or plated or plating)).clm.	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:53
L4	21262	I1 or I2 or I3	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:53
L5	309287	(semiconductor or wafer).clm.	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:53
L6	32319	(anneal or anneals or annealed or annealing).clm.	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:54
L7	4286	(temperature adj gradient).clm.	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:54
L8	6	I4 and I5 and I6 and I7	US-PGPUB; USPAT	ADJ	ON	2008/06/06 09:54

6/ 6/ 08 9:56:03 AM